MEARS

Serial No. 10/717,370

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IN THE CLAIMS:

Claims 1-76 (canceled).

77. (New) A method for making a semiconductor device comprising:

forming a superlattice comprising a plurality of stacked groups of layers; and

each group of layers of the superlattice comprising four stacked base semiconductor monolayers defining a base semiconductor portion and an energy band-modifying layer thereon;

the energy-band modifying layer comprising at least one non-semiconductor monolayer constrained within a crystal lattice of adjacent base semiconductor portions.

- 78. (New) A method according to Claim 77 wherein the superlattice also has a common energy band structure therein.
- 79. (New) A method according to Claim 77 wherein the superlattice has a higher charge carrier mobility in at least one direction than would otherwise be present.
- 80. (New) A method according to Claim 79 wherein the higher charge carrier mobility results from a lower conductivity effective mass for the charge carriers in a parallel direction than would otherwise be present.

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81. (New) A method according to Claim 80 wherein the lower conductivity effective mass is less than two-thirds the conductivity effective mass that would otherwise occur.

- 82. (New) A method according to Claim 79 wherein the charge carriers having the higher mobility comprise at least one of electrons and holes.
- 83. (New) A method according to Claim 77 wherein each base semiconductor portion comprises silicon.
- 84. (New) A method according to Claim 77 wherein each energy band-modifying layer comprises oxygen.
- 85. (New) A method according to Claim 77 wherein each energy band-modifying layer is a single monolayer thick.
- 86. (New) A method according to Claim 77 wherein the superlattice further has a substantially direct energy bandgap.
- 87. (New) A method according to Claim 77 wherein the superlattice further comprises a base semiconductor cap layer on an uppermost group of layers.
- 88. (New) A method according to Claim 77 wherein each non-semiconductor monolayer is thermally stable through deposition of a next layer.

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89. (New) A method according to Claim 77 wherein each base semiconductor portion comprises a base semiconductor selected from the group consisting of Group IV semiconductors, Group III-V semiconductors, and Group II-VI semiconductors.

- 90. (New) A method according to Claim 77 wherein each energy band-modifying layer comprises a non-semiconductor selected from the group consisting of oxygen, nitrogen, fluorine, and carbon-oxygen.
- 91. (New) A method according to Claim 77 wherein forming the superlattice comprises forming the superlattice on a substrate.
- 92. (New) A method according to Claim 77 further comprising doping the superlattice with at least one type of conductivity dopant therein.
- 93. (New) A method according to Claim 77 wherein the superlattice defines a channel for a transistor.
- 94. (New) A method for making a semiconductor device comprising:

forming a superlattice comprising a plurality of stacked groups of layers; and

each group of layers of the superlattice comprising four stacked silicon atomic layers defining a silicon portion and an energy band-modifying layer thereon;

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the energy-band modifying layer comprising at least one oxygen atomic layer constrained within a crystal lattice of adjacent silicon portions.

- 95. (New) A method according to Claim 94 wherein the superlattice has a common energy band structure therein.
- 96. (New) A method according to Claim 94 wherein the superlattice has a higher charge carrier mobility in at least one direction than would otherwise be present.
- 97. (New) A method according to Claim 96 wherein the higher charge carrier mobility results from a lower conductivity effective mass for the charge carriers in a parallel direction than would otherwise be present.
- 98. (New) A method according to Claim 96 wherein the charge carriers having the higher mobility comprise at least one of electrons and holes.
- 99. (New) A method according to Claim 94 wherein each energy band-modifying layer is a single atomic layer thick.
- 100. (New) A method according to Claim 94 wherein the superlattice further has a substantially direct energy bandgap.
 - 101. (New) A method according to Claim 94 wherein

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the superlattice further comprises a silicon cap layer on an uppermost group of layers.

- 102. (New) A method according to Claim 94 wherein forming the superlattice comprises forming the superlattice on a substrate.
- 103. (New) A method according to Claim 94 further comprising doping the superlattice with at least one type of conductivity dopant therein.
- 104. (New) A method according to Claim 94 wherein the superlattice defines a channel for a transistor.